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| **Title:** | Gas Assisted Etching and Material Deposition on micro- and nano- scale |
| **Training duration:** | *3 days* |
| **Training cost:** | *Groups of 1 – 3 trainees, US$3600 per group* |
| **Background required:** | *Basic FIB operator training, basic background in physics, chemistry, or material science* |
| **Student Objective:** | *Understanding basics of GAE and material deposition, influence of beam raster parameters on etching and deposition processes, Ga implantation, specifics of in-via milling and deposition* |
| **Equipment:** | *Micrion 2000, 2500, 9000, 9100, 986, 986FC,*<br>*Vectra 986(+), VectraVision, any FIB or FEB equipment* |
| **Syllabus:** | *TBD, available online by June 30, 2004* |